



COPY OF PAPERS
ORIGINALLY FILED

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

re Application of:

Inventors: Katsuji Iguchi, Sheng Teng Hsu,
Yoshi Ono and Jer-shen Maa

Serial No.: 10/035,503

Filed: October 25, 2001

Title: METHOD OF FABRICATING
DEEP SUB-MICRON CMOS
SOURCE/DRAIN WITH MDD
AND SELECTIVE CVD SILICIDE

PATENT APPLICATION

Attorney Docket No.
SLA 0636

POWER OF ATTORNEY BY ASSIGNEE

Sharp Laboratories of America, Inc., a corporation of the State of Washington, Assignee of the entire right, title and interest in and to the above-identified patent application by an assignment document filed herewith, hereby appoints David C. Ripma, Reg. No. 27,672, Matthew D. Rabdau, Reg. No. 43,026, and Scott C. Krieger, Reg. No. 42,768. as its attorneys with full power of substitution and revocation, to prosecute this application and to transact all business in the Patent and Trademark Office connected therewith; said appointment to be to the exclusion of the inventor and the inventor's attorneys in accordance with the provisions of 37 C.F.R. §3.71.

Pursuant to 37 C.F.R. §3.73(b) the undersigned submits herewith the original of an assignment document from the inventor or inventors to Assignee, together with a cover sheet and the fee for recording same. The

assignment has been reviewed and, to the best of the undersigned's knowledge and belief, title is in the Assignee. The undersigned, whose title is supplied below, is empowered to sign this power of Attorney on behalf of the Assignee.

Please direct all correspondence connected with this application to:

David C. Ripma, Patent Counsel
Sharp Laboratories of America, Inc.
5750 NW Pacific Rim Boulevard
Camas, WA 98607
Telephone: (360) 834-8754
Facsimile: (360) 817-8505

**COPY OF PAPERS
ORIGINALLY FILED**

Assignee:

Sharp Laboratories of America, Inc.

By: Jon K. Clemens
Title: Jon K. Clemens
President & CEO

Date: March 6, 2002